## **NNCI** Computation

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### **Objectives**

- To facilitate access to the modeling and simulation capabilities and expertise
- To identify the strategic areas for growth
- To promote and facilitate the development of the new capabilities.

An inventory of available modeling and simulation resources and expertise is being complied. The directory is hosted by nanoHub.org.

8 supercomputers or major computing clusters are available in various sites.

https://www.nnci.net/computation-resources



# Modeling and Simulation @ NCI-SW



Dragica Vasileska, ASU (NCI-SW)



# **Device Simulation**

#### Conventional MOSFET



### LDMOS: Lateral Double-Diffused MOSFET



#### VDMOS:Vertical Double-Diffused MOSFET



An in-house full-band Monte Carlo (FBEMC) device simulation tool is developed and validated.





Dragica Vasileska, ASU (NCI-SW)

# **Device and Process Simulation Course**

Developed ONLINE Graduate Level Semiconductor Device and Process Modeling Class (primarily focused on <u>Silvaco</u> device/process modeling).

27 students are currently taking the class at ASU from all over United States.





Dragica Vasileska, ASU (NCI-SW)

## Contributions to nanoHUB.org

### **Developed Bound States Calculation Lab:**

ind States Calculation Lab	X Terminate 🕩 Keep for later
<b>put → @</b> Simulate	=
Confining Potential : Square Well Effective mass er of Energy Levels : Trangular Well V-Shaped Well	2
Well Wit	dth (in nm) : 10
Well Dep	oth (in eV) : 0.5
se yes if you want to have default mesh spacing, els	se choose no: 🔍 🗐 🖿 yes
	ing (in nm) : 0.1

Table 1: Overview	
Item	Value
Contributions:	378
Rank by Contributions:	3 / 2375
First Contribution:	09 Mar 2005
Last Contribution:	19 Mar 2020
<b>Citations on Contributions:</b>	181
Usage in Courses/Classrooms:	7,516 users served in 480 courses from 47 institutions

235 users/6 months (*since April 2020*)



X Terminate









# **CNF** Computing Capabilities

Resources available remotely during COVID-19

- Nanoscale simulation computing cluster
  Runs Scientific Linux 7 w OpenHPC & Slurm; Bring Your Own License!
- Pseudopotential Virtual Vault
  Online web database of over 1100 pseudopotential or Projected
  Augment Wave Method (PAW) files
- Remote access to software tools via "CNF Thin" Hotdesking service CAD (BEAMER, L-Edit, Java GDS, AutoDesk); Simulation (Coventor, Cadence, PROLITH, Layout LAB, TRACER); Image/Data Analysis (ProSEM, NanoScope Analysis, WinFLX)
- Virtual CAD Room
  Remote access to a virtual CNF CAD Rm Windows desktop w CNF SW
- AWS Conversion Cloud Large memory or CPU or long running CAD conversion jobs





# 2D Materials Database on MNIC Website



Includes more than 45 2D n



WSe2			
Property	Description/Value		
	Bulk	Monolayer	
Lattice constant (a)	3.28 Å [1]	3.32 Å [2]	
Molar mass	341.76 g/mol [3, 4]	341.76 g/mol [3, 4]	
Band gap type	Indirect [5]	Direct [5]	
Band gap energy	1.2 eV (experimental) [6]	1.65 eV (experimental) [5] 1.25 eV (calculation) [2]	
Coordination geometry	Trigonal prismatic (W <sup>IV</sup> ), Pyramidal (Se <sup>-2</sup> ) [3, 4, 7]	Trigonal prismatic (W <sup>IV</sup> ), Pyramidal (Se <sup>-2</sup> ) [3, 4,7]	
Crystal structure	hP6, space group P6 <sub>3</sub> /mmc, No 194 [3,7]	hP6, space group P6 <sub>3</sub> /mmc, No 194 [3, 7]	
Appearance	Grey to black solid [3, 7]		
Group	Transition Metal Dichalcogenide [7]	Transition Metal Dichalcogenide [7]	
Spin-orbit splitting		0.47 eV [2]	
Poisson's ratio		0.19 [2]	
Cohesive energy per unit cell		15.45 eV [2]	
Charge transfer of W atom	0.96 e [2]	0.96 e [2]	
In-plane stiffness		115.52 N/m [2]	
Density	9.32 g/cm <sup>3</sup> [3]	9.32 g/cm <sup>3</sup> [3]	
Melting point	1500 °C [8]		
Exciton binding energy		0.79 eV [9]	
W-Se bond length		2.55 Å [2]	
Dielectric constant (ɛ)		Real part (ε1)=~22, Imaginary part (ε2)=~10 (at 1.7 eV incident photon energy) [10]	
Effective masses		$m_e = 0.53 m_o, m_h = 0.52 m_o$ [11]	
Effective Bohr radius			
Thermal expansion coefficient		11.08×10 <sup>-6</sup> /°C [12]	
Bulk Modulus (B)			
Refractive Index		5.68 [13]	
Carrier mobility in WSe2			
Thicknesses	BN/SiO <sub>2</sub> /Si substrate	SiO <sub>2</sub> /Si Substrate	
8 nm		~350 cm <sup>2</sup> /V.Sec (hole) [14]	
Monolayer	~31 cm <sup>2</sup> /V.Sec [15]		
Bulk			



# Modeling @ GT(Ferroelectrics, Antiferromagnets, Multiferroics, Magnets & their Heterojunctions



#### IEEE-Trans. Electron Devices, 2020



Magnetization Dynamics of a Single-Domain BiFeO3 Nanoisland

IEEE-Trans. Magnetism, 2020





Dynamic Response of BFO/CoFe Heterostructure To appear in Nano Letters



Funded by Intel Co. and SRC

# Looking Ahead (Years 6-10)

- The goal is to promote wider use of process and device simulation tools.
- Work closely with Prof. Vasileska (NCI-SW) and Prof. Register (TNF).
- Offer "Device and Process Simulation Course" developed by Prof. Vasileska at the network level.
- Invited e-seminars on various modeling and simulation topics:
  - Simulation approaches for various research areas
  - Emerging modeling and simulation trends
  - Examples of collaborations among theorists and experimentalists
- Promote and help public release of internally developed modeling/simulation tools

